

FIG. 1 is a schematic diagram of a system for processing a substrate.

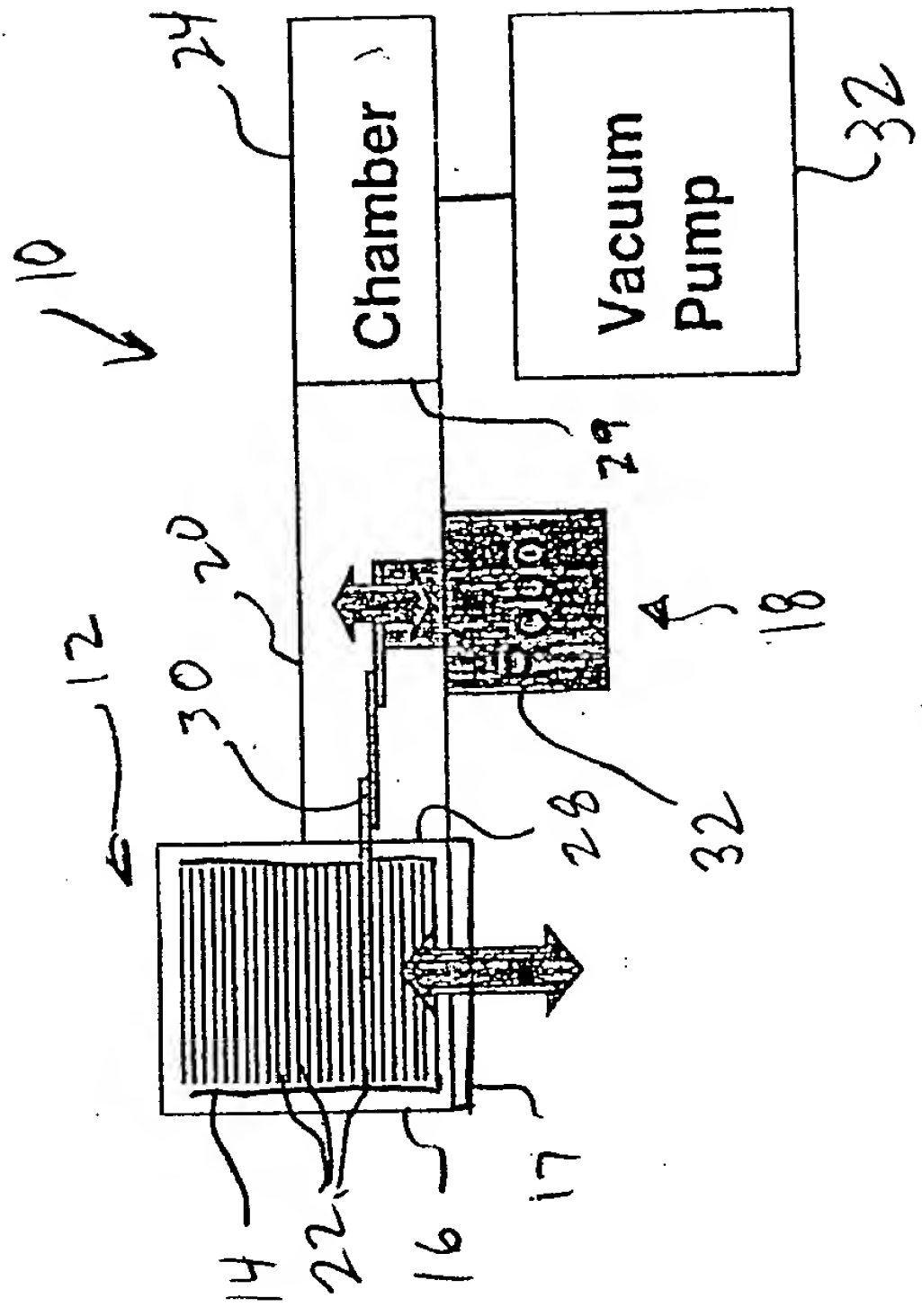


Fig-1

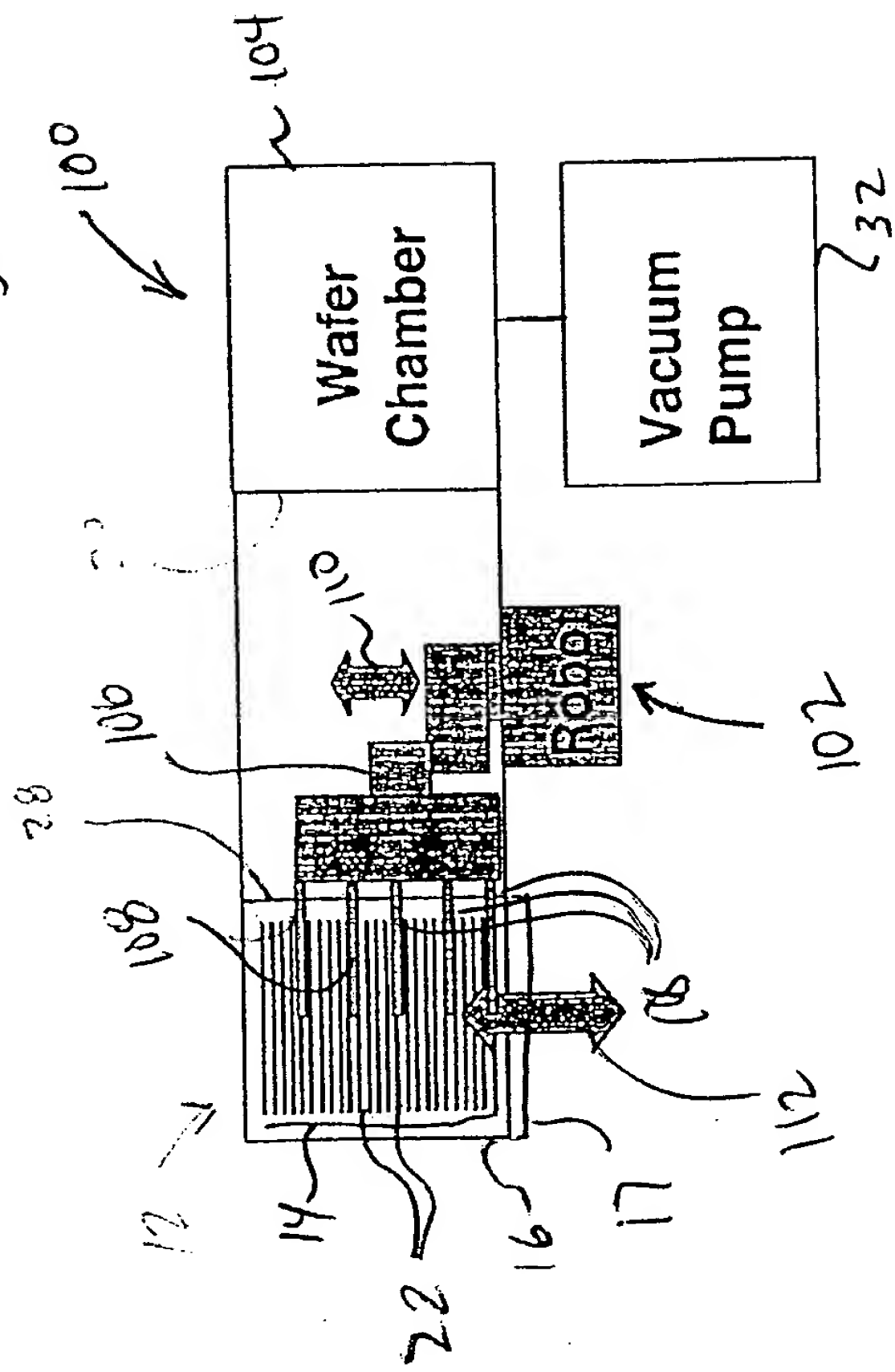


Fig-5A

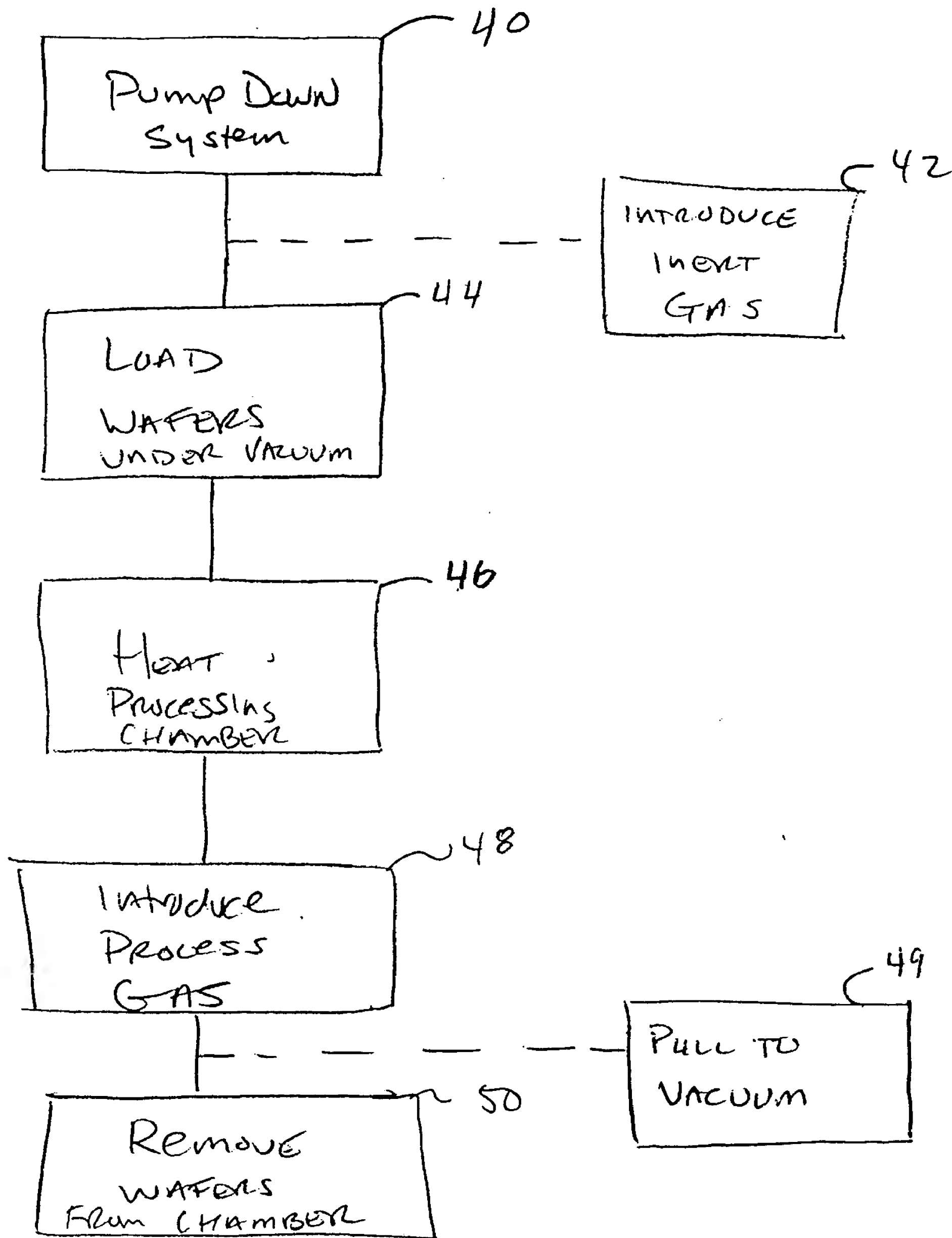


Fig- 2

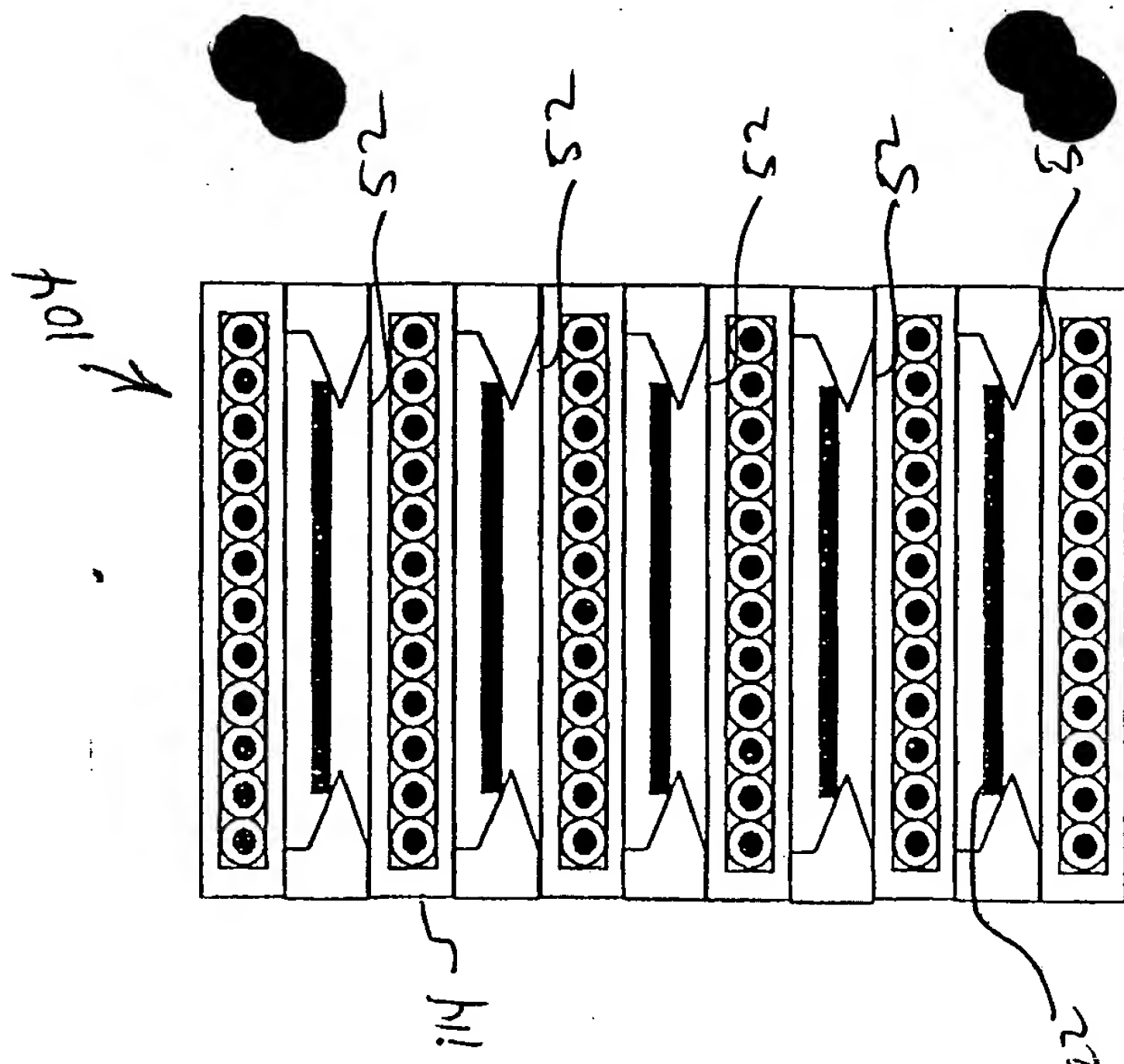
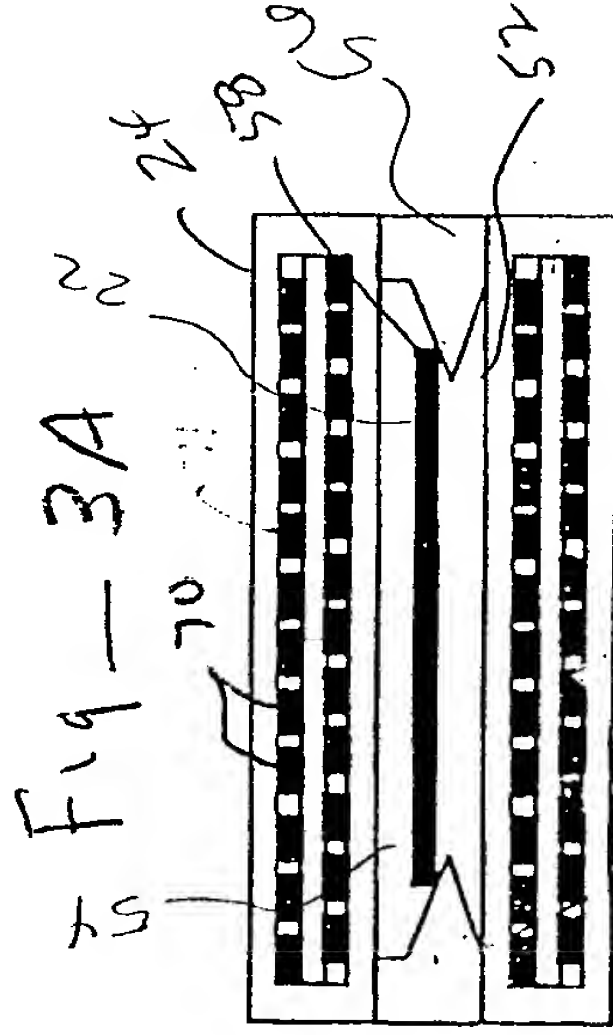
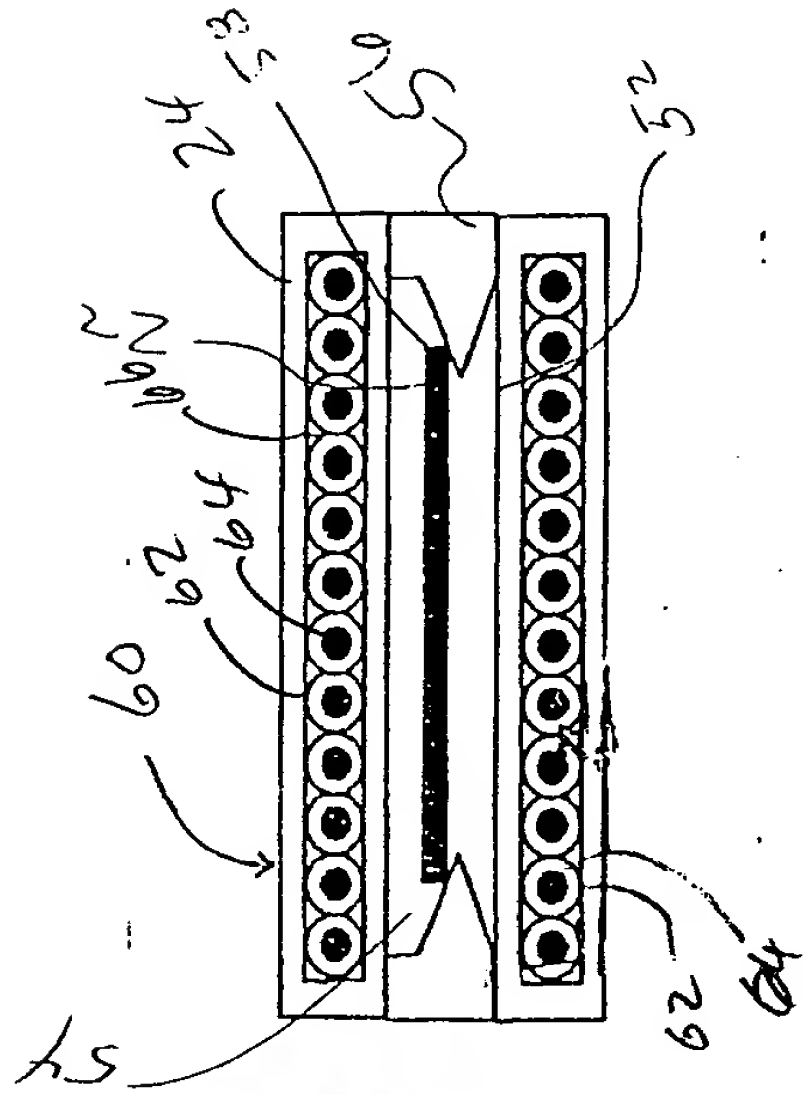
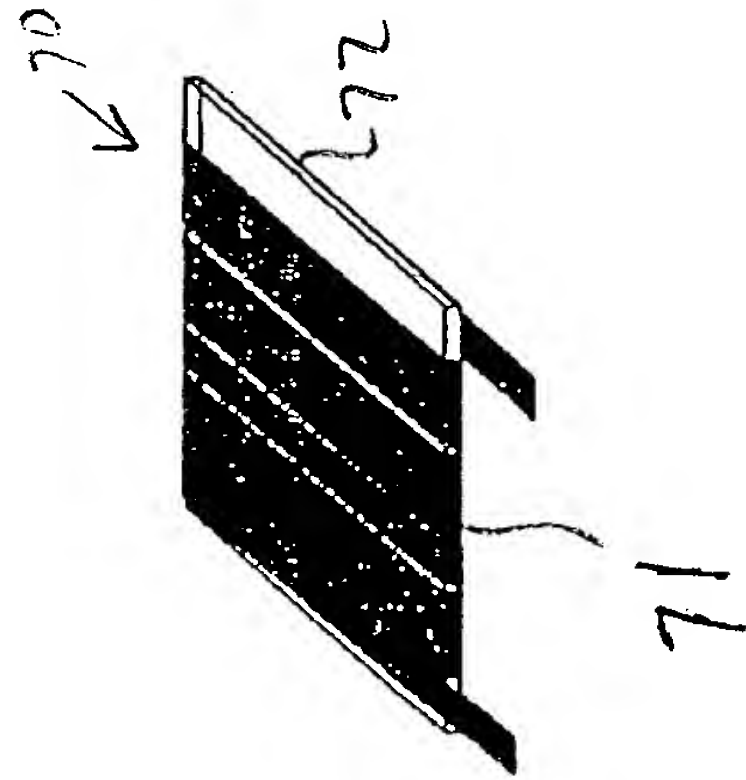
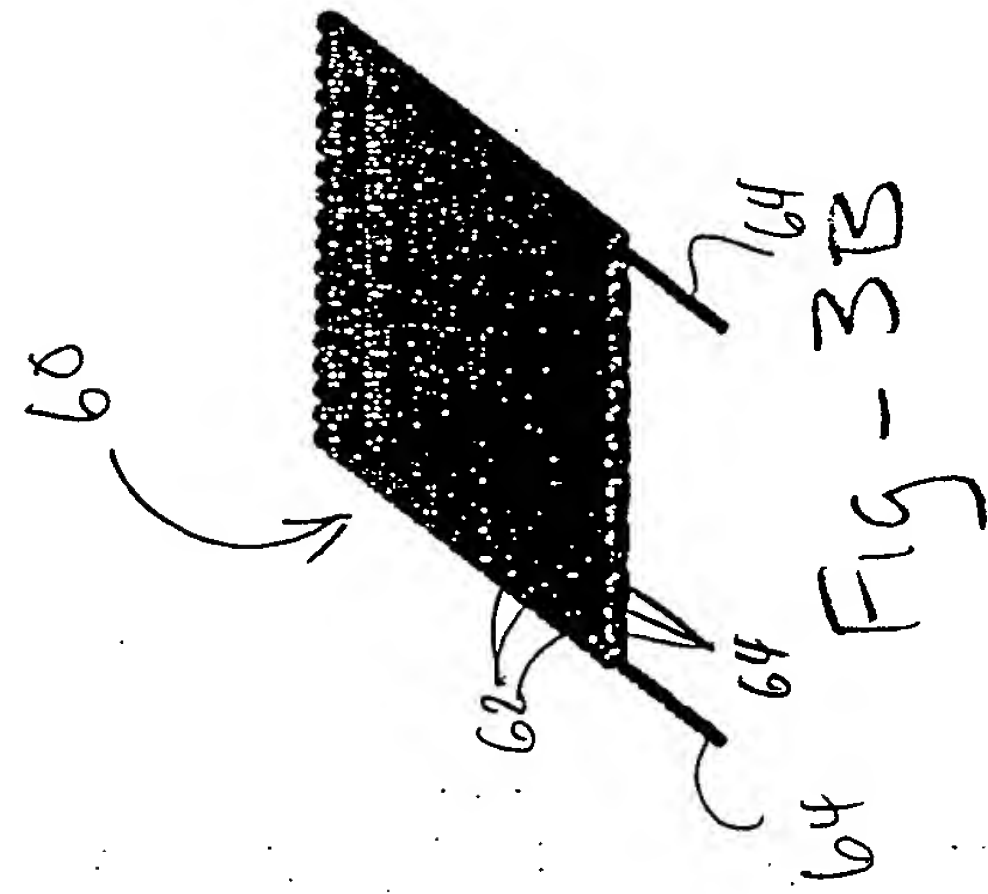


Fig-4A

FIG. 6 is a perspective view of the device in accordance with the present invention.

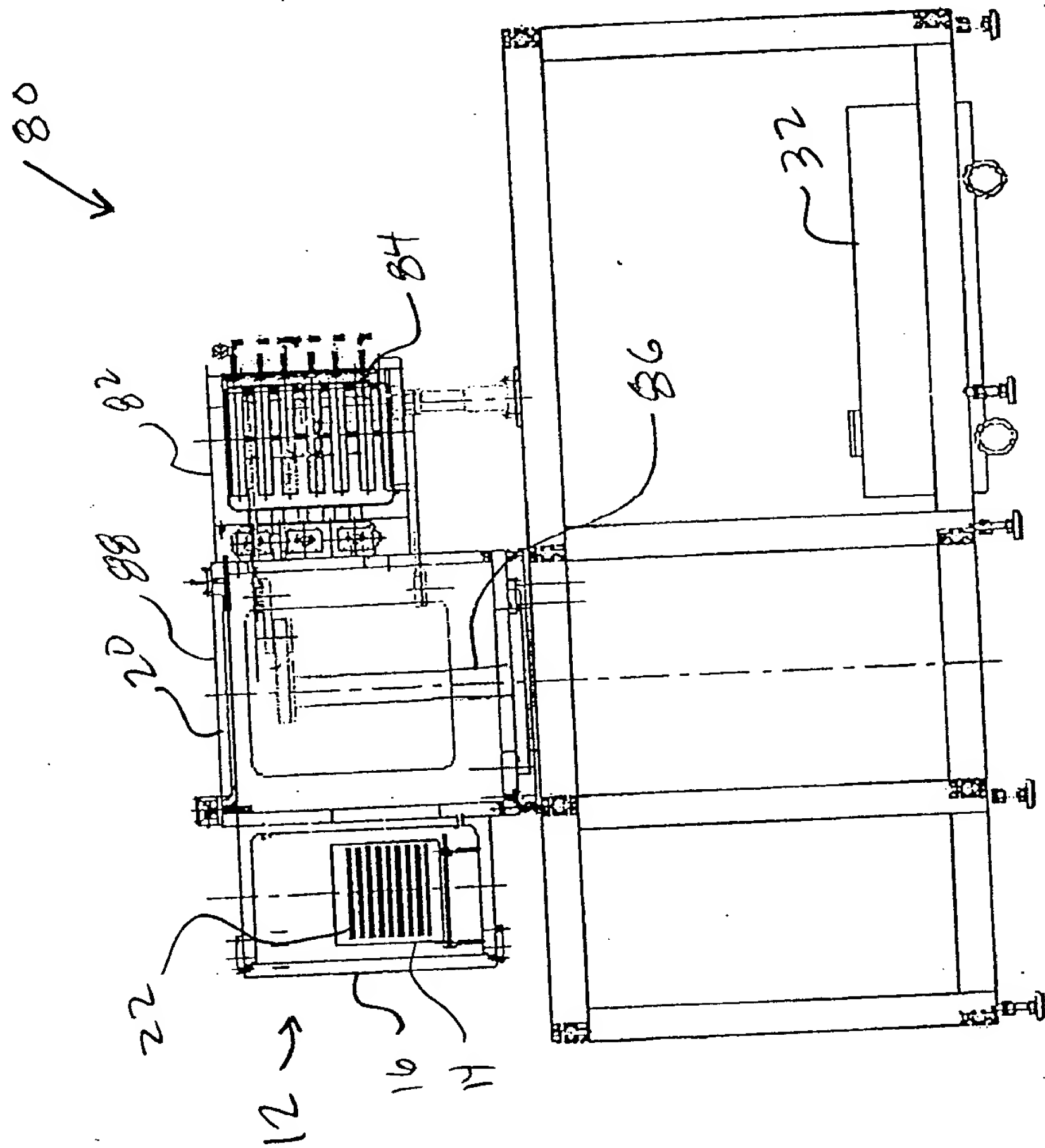
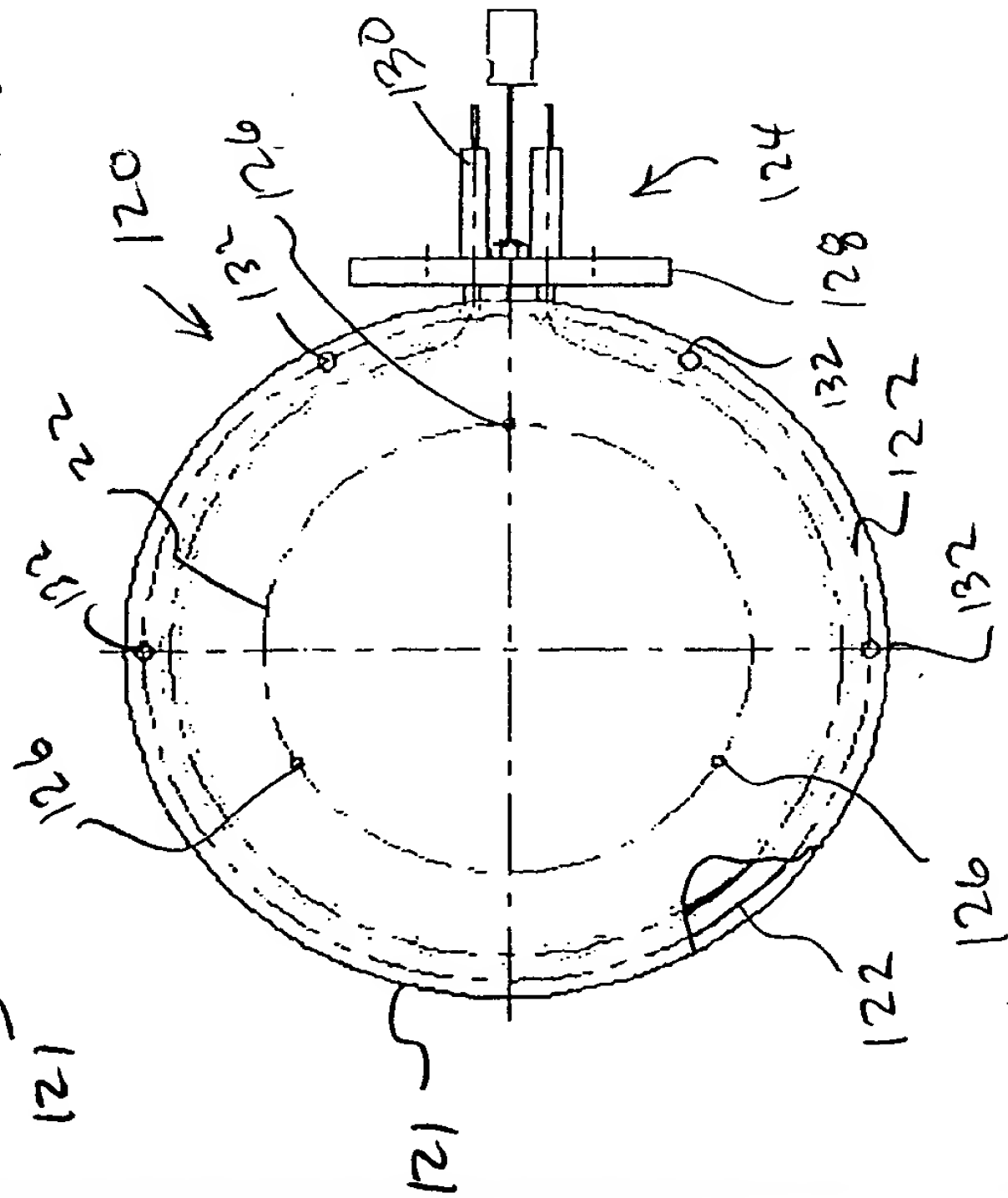
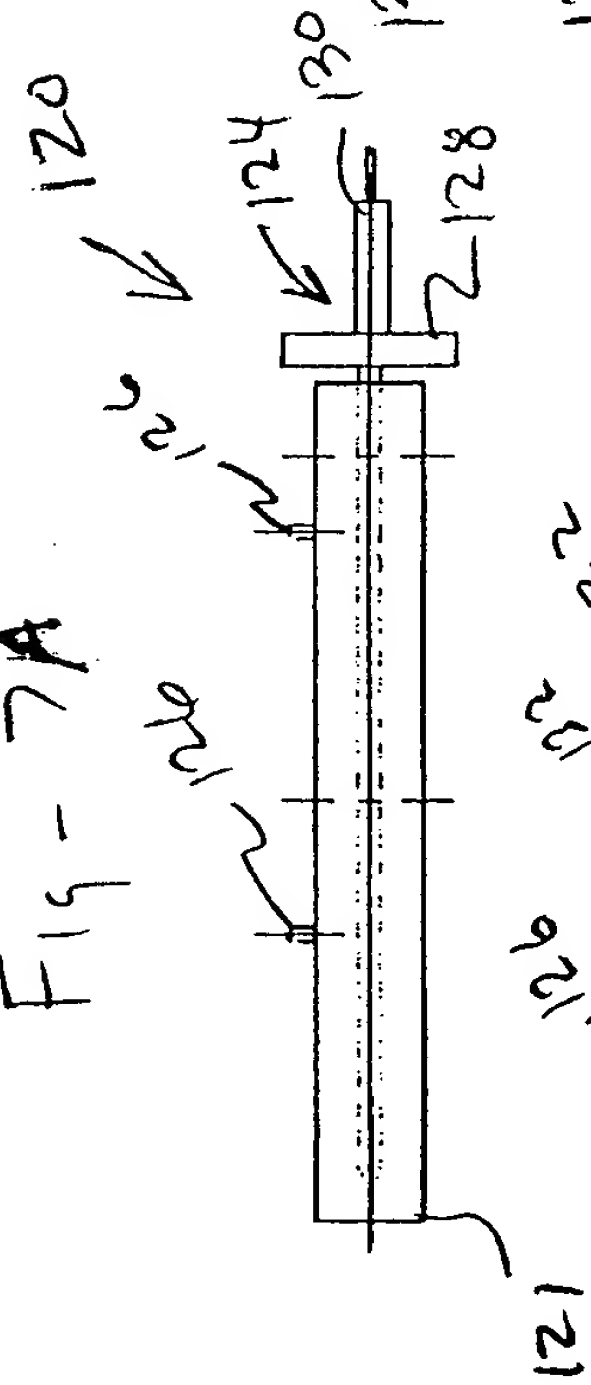
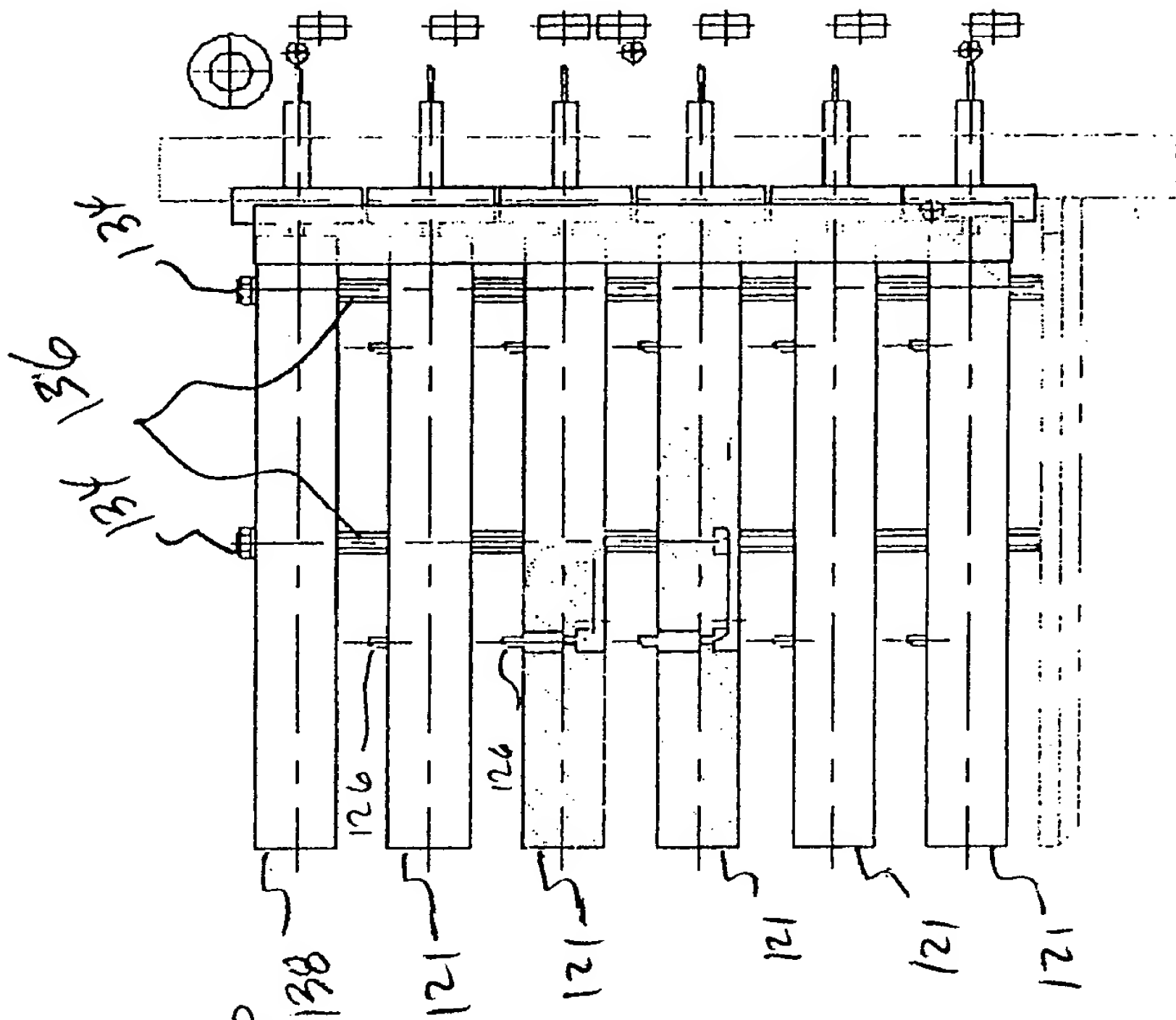


Fig-6

Fig-7A



Fg. 7B



22-5-72

Pressure / Temperature

Temp —  
Pressure ---

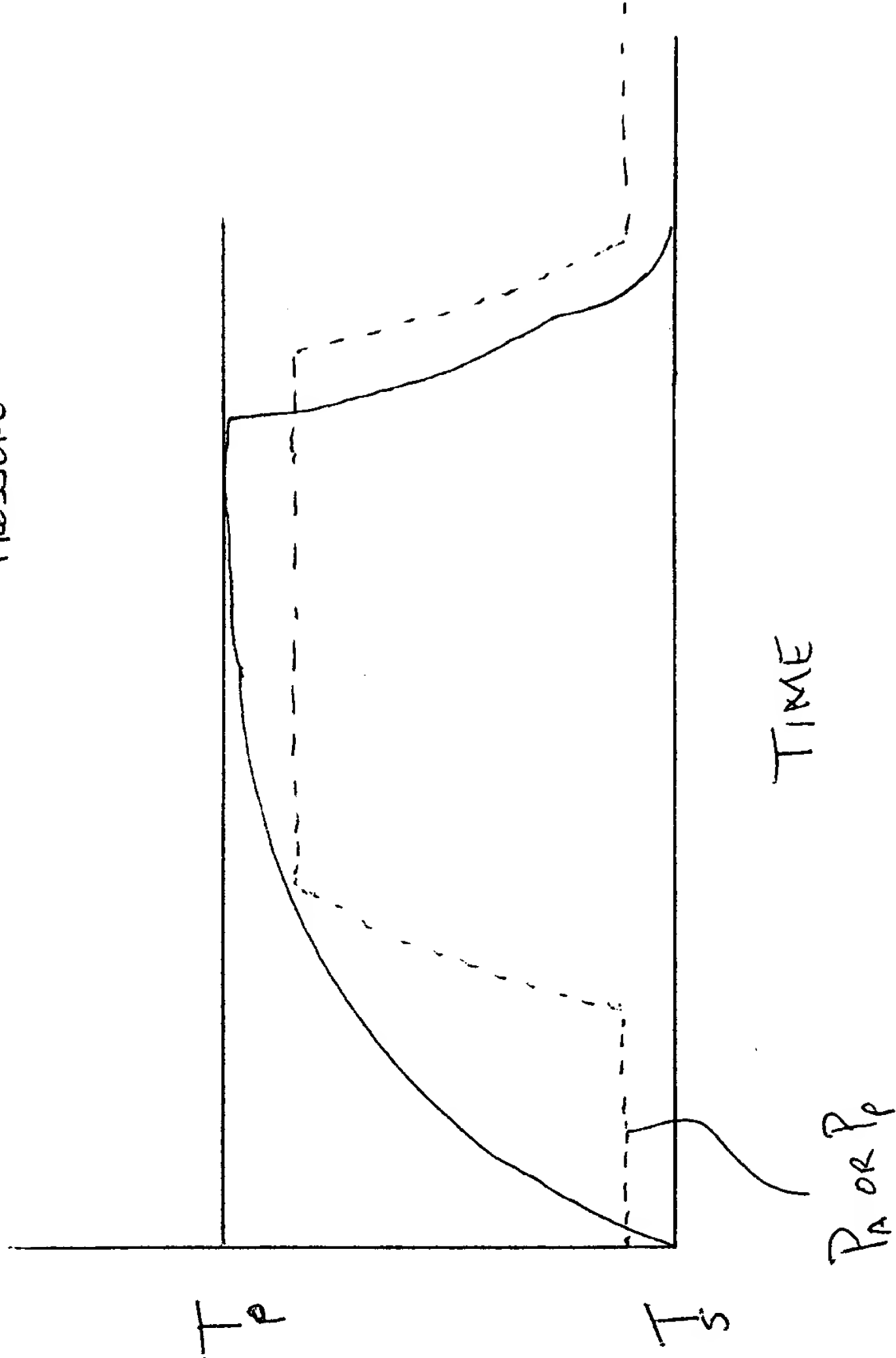


FIG. 8